

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No. : Natl. Phase of PCT/JP2003/011137
Applicant(s) : Mitsuru UEDA *et al.*
Filed : herewith
TC/A.U. :
Examiner :
Docket No. : 28955.1048
Customer No. : 27890
Title : PHOTORESIST BASE MATERIAL, METHOD FOR
PURIFICATION THEREOF, AND PHOTORESIST COMPOSITIONS

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

PRELIMINARY AMENDMENT

Sir:

Prior to examination of the instant application, please amend the above-identified application as follows:

Amendments to the Claims to be entered for consideration by the Examiner prior to examination are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 11 of this paper.